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APPLICATION NO.	FII	LING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/603,091	06/25/2003		Shuichi Kikuchi	492322013000	1918
25227	25227 7590 05/07/2004		EXAMINER		
MORRISO 1650 TYSO		RSTER LLP	JACKSON JR, JEROME		
SUITE 300				ART UNIT	PAPER NUMBER
MCLEAN,	VA 22102	2	2815		

DATE MAILED: 05/07/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)				
		10/603,091	KIKUCHI ET AL.				
	Office Action Summary	Examiner	Art Unit				
		Jerome Jackson Jr.	2815				
Period fo	The MAILING DATE of this communication ap or Reply	pears on the cover sheet with th	e correspondence address				
THE   - External after   - If the   - If NO   - Failu   Any I	ORTENED STATUTORY PERIOD FOR REPL MAILING DATE OF THIS COMMUNICATION. nsions of time may be available under the provisions of 37 CFR 1. SIX (6) MONTHS from the mailing date of this communication. period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period re to reply within the set or extended period for reply will, by statutively received by the Office later than three months after the mailing patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, may a reply but by within the statutory minimum of thirty (30) will apply and will expire SIX (6) MONTHS fe, cause the application to become ABANDC	e timely filed  days will be considered timely.  rom the mailing date of this communication.  DNED (35 U.S.C. § 133).				
Status							
1)[	Responsive to communication(s) filed on						
2a) <u></u> □	This action is <b>FINAL</b> . 2b)⊠ This action is non-final.						
3) 🗌	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Dispositi	on of Claims						
5)□ 6)⊠ 7)⊠	Claim(s) <u>1-9</u> is/are pending in the application. 4a) Of the above claim(s) is/are withdra Claim(s) is/are allowed. Claim(s) <u>1-5 and 7-9</u> is/are rejected. Claim(s) <u>6</u> is/are objected to. Claim(s) are subject to restriction and/o						
Applicati	on Papers						
9) 🗌 🤈	The specification is objected to by the Examino	er.					
10) 🔲	The drawing(s) filed on is/are: a)☐ acc	cepted or b) objected to by the	ne Examiner.				
	Applicant may not request that any objection to the	drawing(s) be held in abeyance.	See 37 CFR 1.85(a).				
11)	Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the E						
Priority u	ınder 35 U.S.C. § 119						
a)[	Acknowledgment is made of a claim for foreign  All b) Some * c) None of:  1. Certified copies of the priority document  2. Certified copies of the priority document  3. Copies of the certified copies of the priority application from the International Burea	ts have been received. ts have been received in Applic prity documents have been rece u (PCT Rule 17.2(a)).	cation No eived in this National Stage				
* S	see the attached detailed Office action for a list	of the certified copies not rece	ived.				
Attachment	• •						
	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948)	4) 🔲 Interview Summ Paper No(s)/Mai					
3) 🔲 Inform	ration Disclosure Statement(s) (PTO-1449 or PTO/SB/08)  No(s)/Mail Date		al Patent Application (PTO-152)				

Application/Control Number: 10/603,091

Art Unit: 2815

Figure 14 should be designated by a legend such as --Prior Art-- because only that which is old is illustrated. See MPEP § 608.02(g). A proposed drawing correction or corrected drawings are required in reply to the Office action to avoid abandonment of the application. The objection to the drawings will not be held in abeyance.

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.
- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 1,3-5,7 and 8 are rejected under 35 U.S.C. 102(b) as being anticipated by Kitamura '842.

Kitamura teaches a DMOS structure including a substrate 1 of p conductivity type, a gate insulation film 6, a gate electrode 7, a source 5 of n conductivity type, an n+high impurity drain layer 8, an n low impurity drain layer 2, and a p type buried layer 9. Accordingly claim 1 is anticipated. Claim 3 is anticipated because p region 9 does not contact region 2. Claim 4 is rejected as drain region 8 is formed deeper than source region 5. Claim 5 is rejected as above. Claim 7 is rejected as region 2 is deeper than region 8. Claim 8 is rejected as region 8 of Kitamura comprises areas or "layers" of material which are disposed at the same depth as the source region and a second

"layer" below the depth of the source region. Note that the regions in Kitamura comprise atomic layer upon atomic layer of doped silicon material and are in essence "layered" materials.

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1- are rejected under 35 U.S.C. 103(a) as being unpatentable over Kitamura with applicant's prior art admissions (APP).

Prior art figure 14 of applicant shows a conventional design where the gate electrode extends onto a thicker field oxide to increase the breakdown voltage. It would have been obvious to have practiced the breakdown voltage designs of Kitamura with an extended gate electrode and thick oxide from APP in order to increase breakdown voltage or form in a DMOS device. Claims 2 and 9 are obvious structure.

Claim 6 is objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Sogo is relevant art.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Jerome Jackson Jr. whose telephone number is 571 272 1730. The examiner can normally be reached on t-th 9-5.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas can be reached on 571 272 1664. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

jj

JEROME JACKSON PRIMARY EXAMINER